PATENT *IFW*Case Docket No. **RYUKA.002AUS**

Date: September 30, 2005

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s) : Kouji Fujiyoshi et al.

App. No. : 10/712,594

Filed : November 12, 2003

For : ELECTRON BEAM EXPOSURE APPARATUS,  
ELECTRON BEAM EXPOSING METHOD, SEMICONDUCTOR  
ELEMENT MANUFACTURING METHOD, AND PATTERN  
ERROR DETECTION METHOD *. O F*

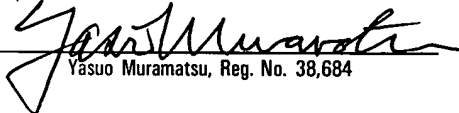
Examiner : William D. Coleman

Art Unit : 2823

I hereby certify that this correspondence and all marked attachments  
are being deposited with the United States Postal Service as first  
class mail in an envelope addressed to: Commissioner for Patents,  
P.O. Box 1450, Alexandria, VA 22313-1450, on

September 30, 2005

(Date)

  
Yasuo Muramatsu, Reg. No. 38,684**TRANSMITTAL LETTER****COMMISSIONER FOR PATENTS  
ALEXANDRIA, VA 22313-1450**

Dear Sir:

Transmitted herewith is a response to office action in the above-identified utility application.

() An extension of time to respond for \* month(s) is hereby requested.

Time Extension Fee:

- () one month (\$120 large entity)
- () two months (\$450 large entity)
- () three months (\$1020 large entity)

Enclosed are:

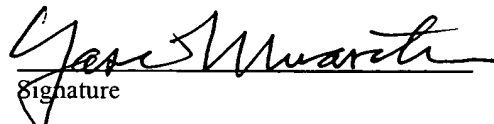
(X) Amendment in 28 pages.

(X) Certified copies of JP 2001-172645 and JP 2002-353141 under 35 U.S.C. 119.

(X) Return prepaid postcard.

SEND ALL CORRESPONDENCE TO:

MURAMATSU & ASSOCIATES  
114 Pacifica  
Suite 310  
Irvine, CA 92618  
Tel: 949-753-1127

  
SignatureYasuo Muramatsu  
Printed Name38,684  
Registration Number